



# An Overview of the UA Maskless Lithography Tool

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Milster Research Group

College of Optical Sciences  
University of Arizona, Tucson, Arizona 85721



# Milster Research Group 2008

- Students:
  - Dongyel Kang
  - Erin Ford
  - Seung Hune Yang
  - Anoop George
  - Taeyoung Choi
  - Yullin Kim
  - Jun Zhang
- Staff:
  - Pramod Khulbe (Research Professor)
  - Young Sik Kim (Visiting Scholar)
  - Jaisoon Kim (Visiting Scholar)
  - Warren Bletscher (Electrical Engineer)
  - Del Hansen (Opto-Mechanical Technician)



# Outline

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- **Motivation**
- **Similarities and Differences Compared to a Commercial Laser Printer**
- **System Characteristics**
- **System Components**
- **Dry Pattern Transfer**
- **Results**
- **Future Work**



# Motivation

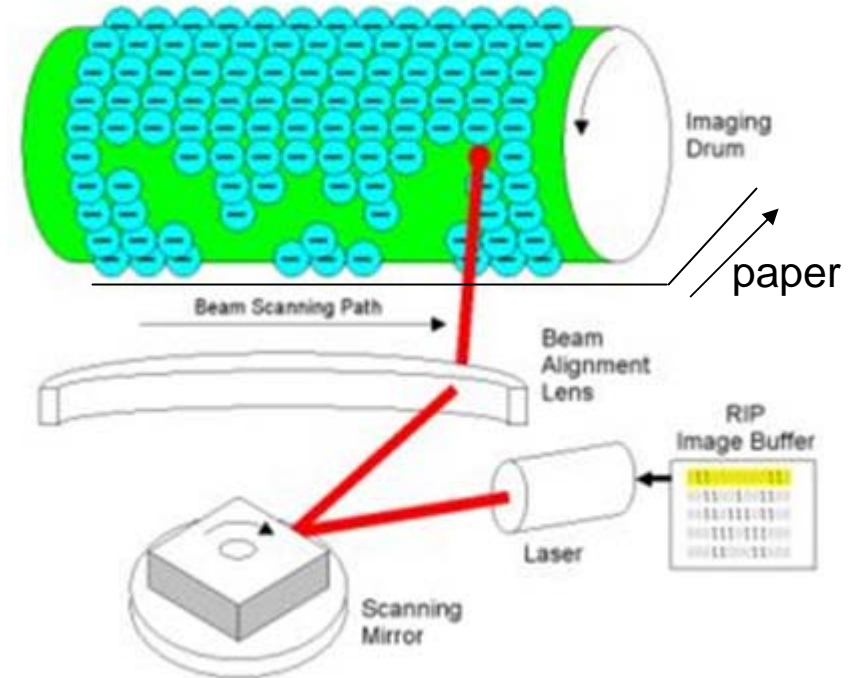
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- Provide computer-generated gray-scale patterning of surfaces for applications including diffractive optical elements (DOEs), computer-generated holograms (CGHs), alignment features, masks, micro-machines, etc.
- Basic Method:
  - Design desired surface profile
  - Print and develop profile in resist
  - Perform other process steps (pattern transfer, Cr etch, alignment and overlay, etc.)

# Commercial Laser Printer

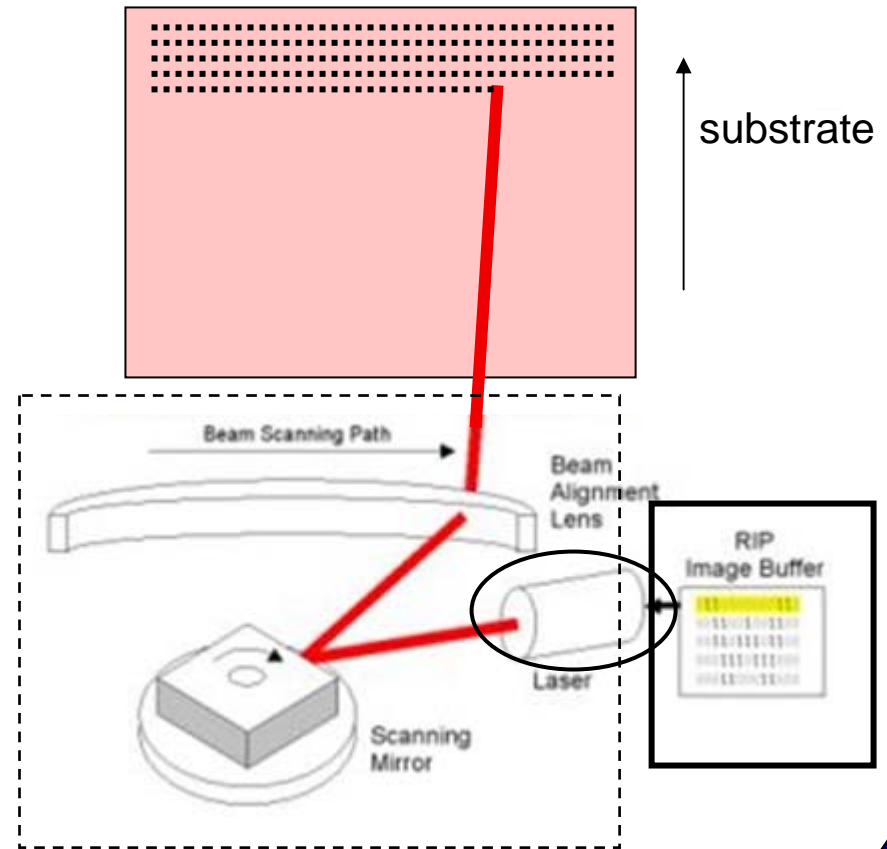
- The laser is aimed at a rotating mirror
- The laser beam is directed through a system of lenses and mirrors onto the photoreceptor
- The beam sweeps across the photoreceptor in straight line
- A stream of rasterized data held in memory turns the laser on and off to form the dots on the cylinder
- Cylinder prints on paper

## Commercial Printer



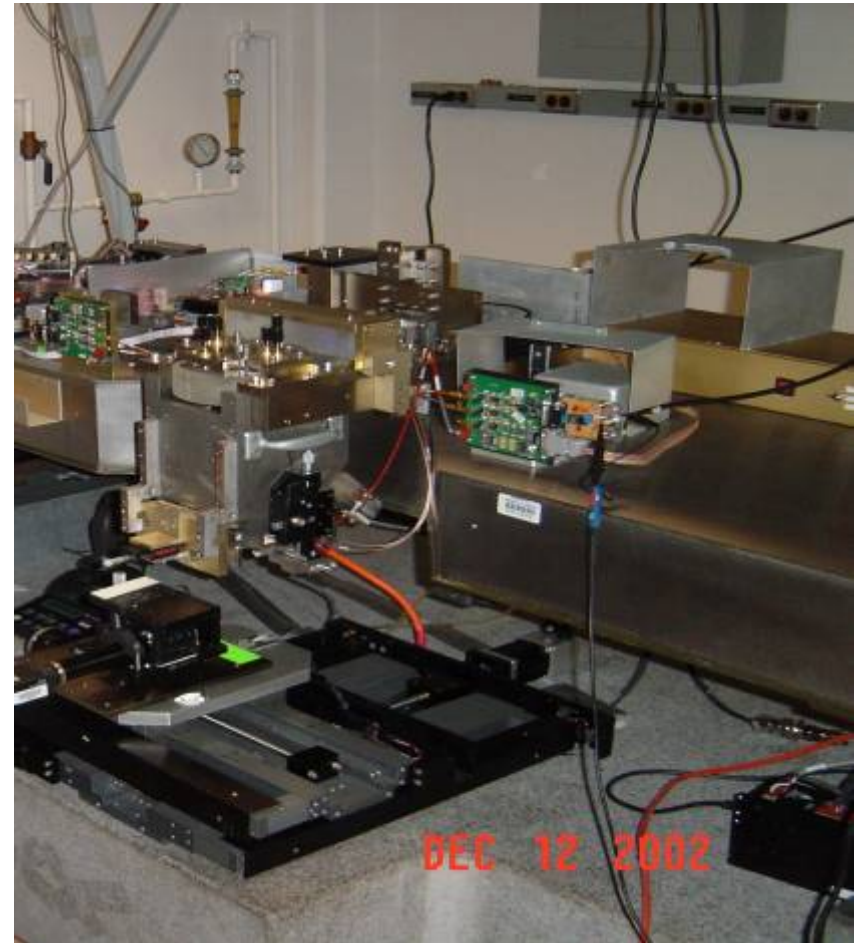
# Differences from a Commercial Laser Printer

- Replace drum and paper with precision stage and substrate with photosensitive material.
- Use high-quality optics
- Use i-line laser with advanced beam control gray-scale modulation
- Use custom, high-performance electronics



# System Characteristics

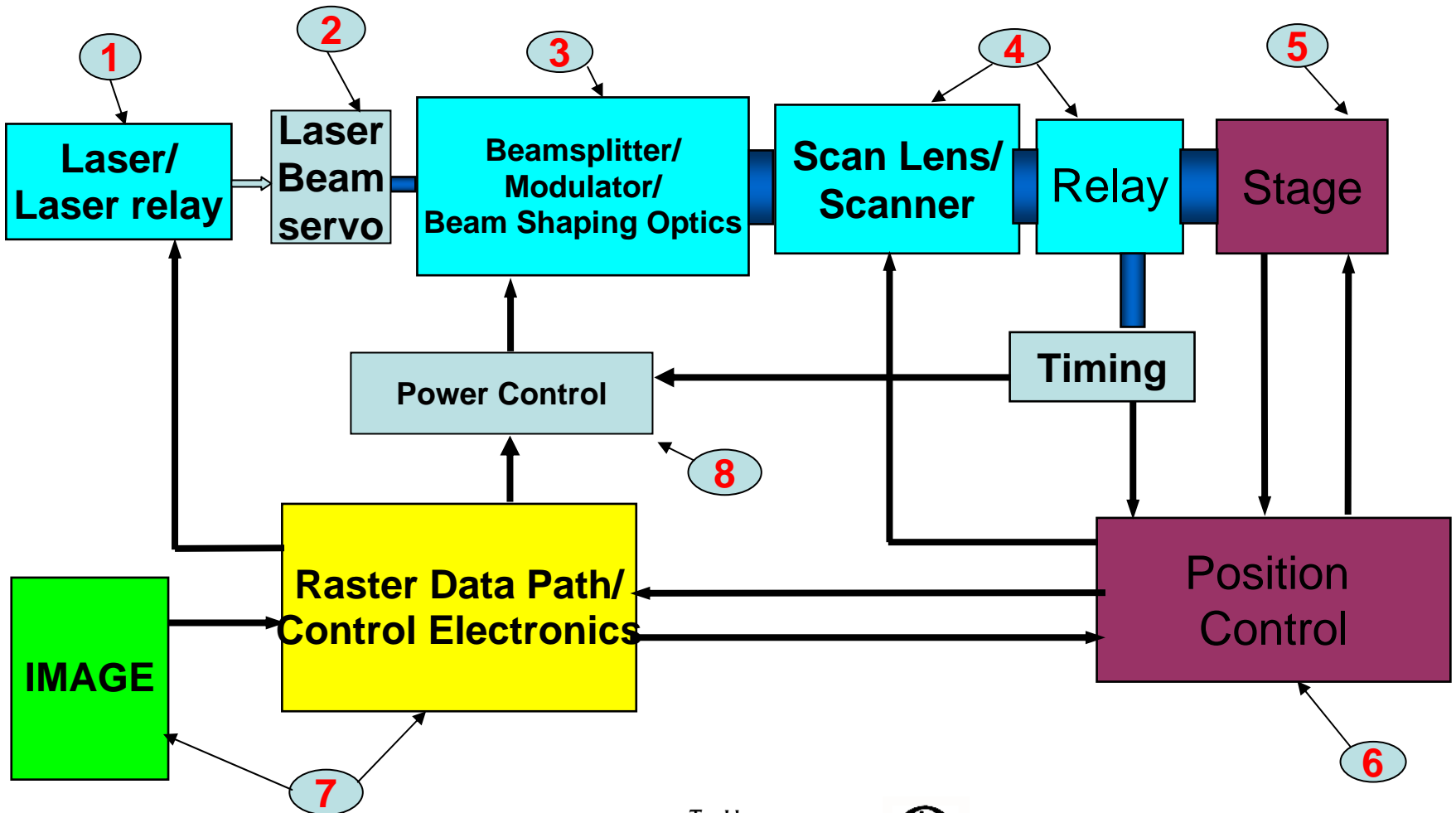
- 20 mm Scan Line Length
- 2.5 micron laser spot size ( $\lambda=365\text{nm}$ )
- 2.1  $\mu\text{m}$  pixel size
- 2 Watt multi line CW Argon Ion Laser
- 30% transmission efficiency
- A/O modulation
- 24 Mpixel/sec data rate
- 10-bit Grayscale Modulation
- 3000 RPM, 12-facet Polygon Mirror on air bearing spindle
- Achromatic optical system from 350-380 nm
- Telecentric image plane
- 90mm by 140mm stitch area



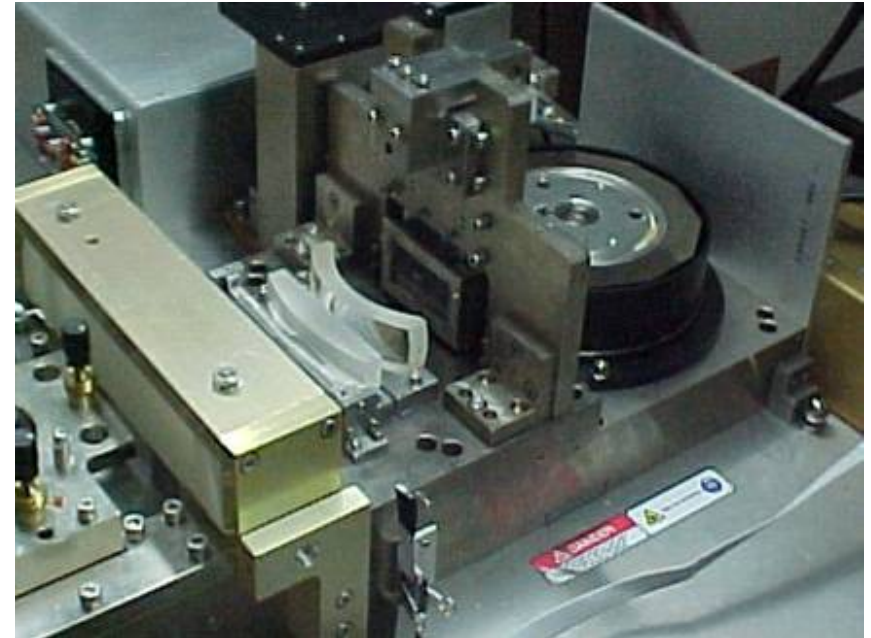
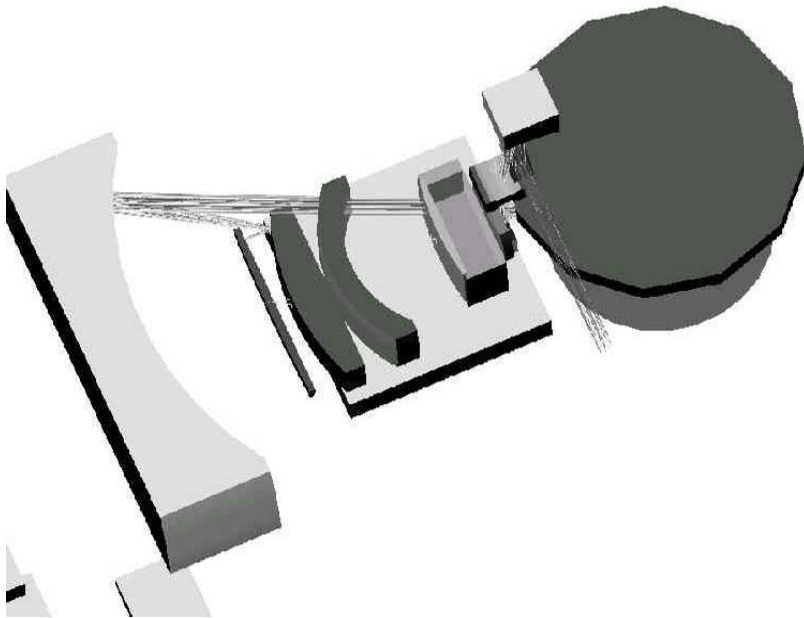


# System Components

*8 basic building blocks*

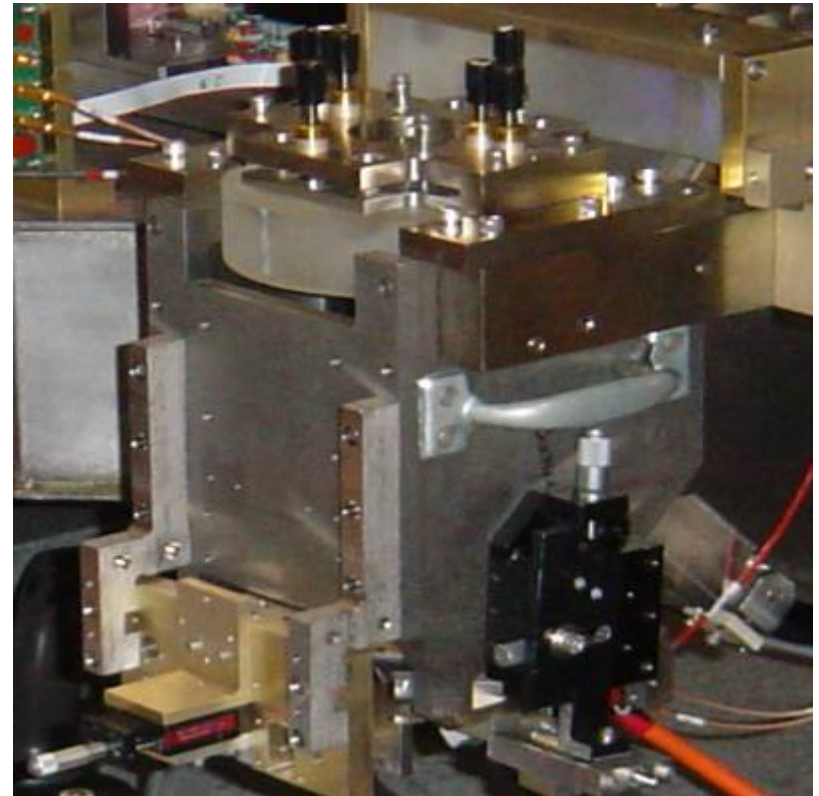
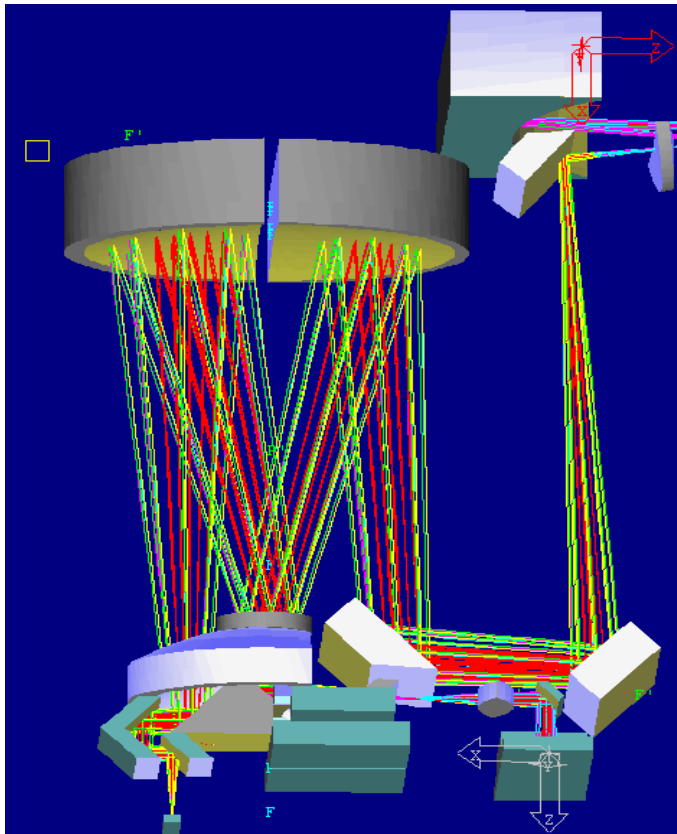


# Scanning System



John Tamkin, UA CGH workshop, March 2007

# Afocal 2.5x Relay

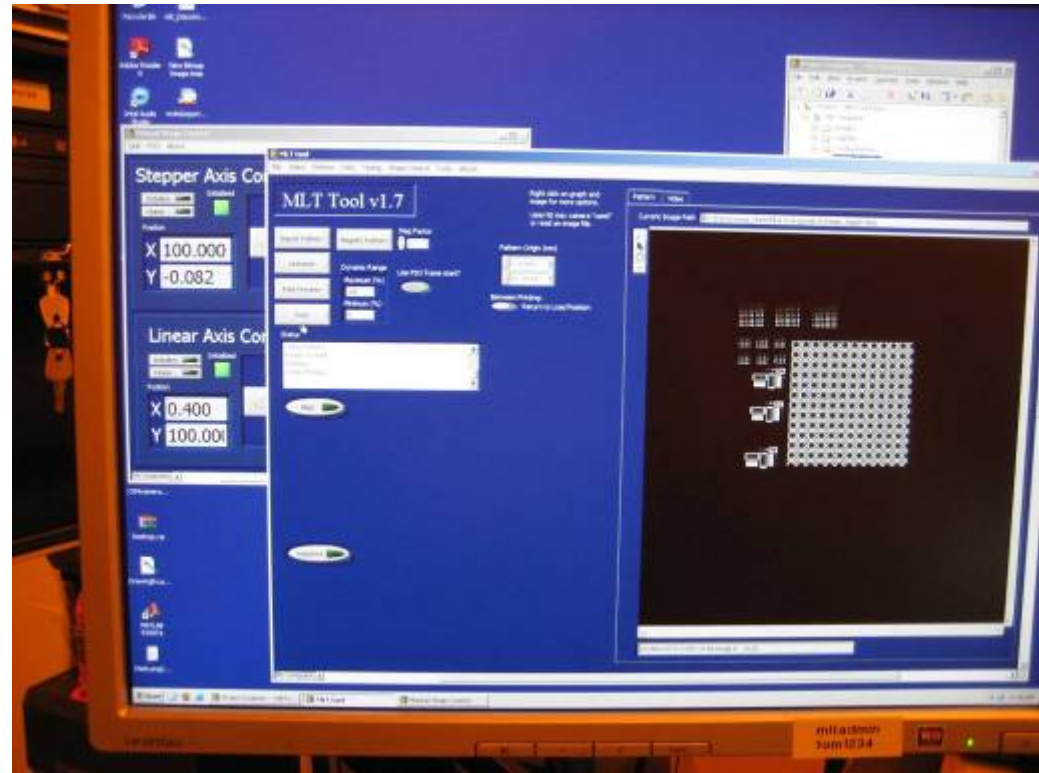


John Tamkin, UA CGH workshop, March 2007



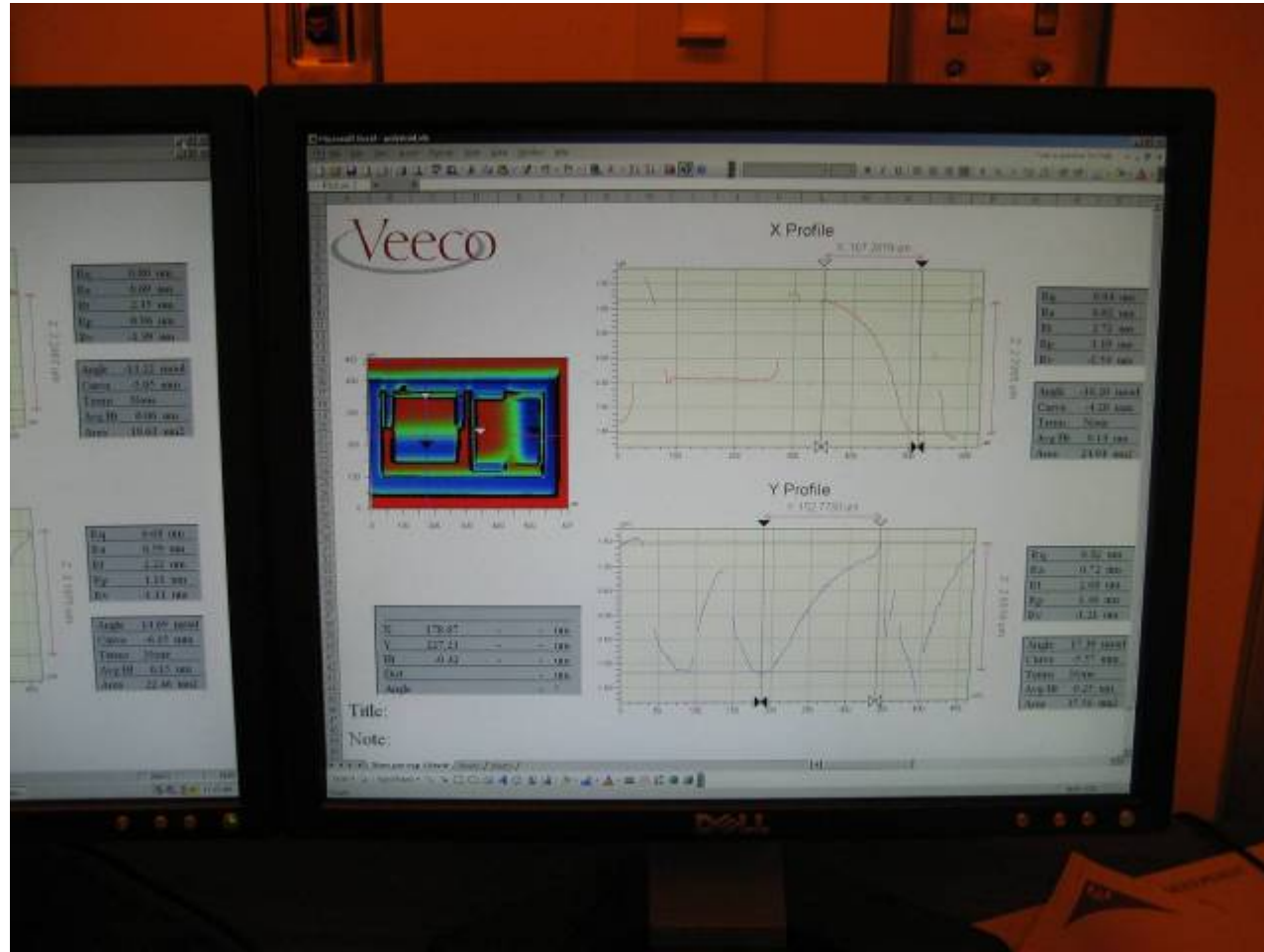
# Control Software

- LabView GUI software
- Accepts bit-map bmp file format (One bmp gray-scale pixel => one address unit on substrate.)





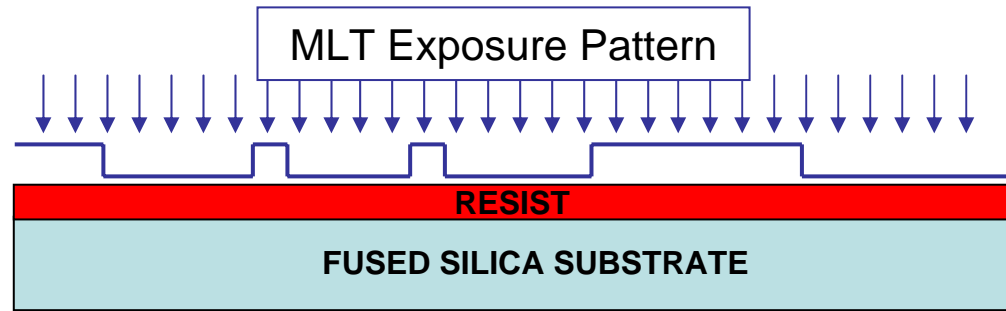
# Veeco NT9800 Measurement



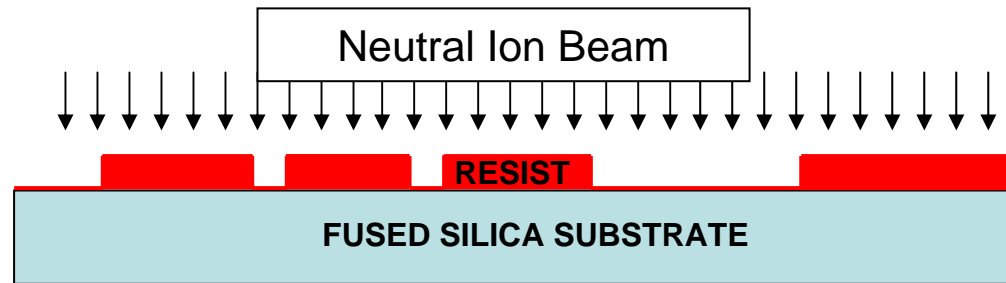


# Dry Pattern Transfer Using an Ion Mill

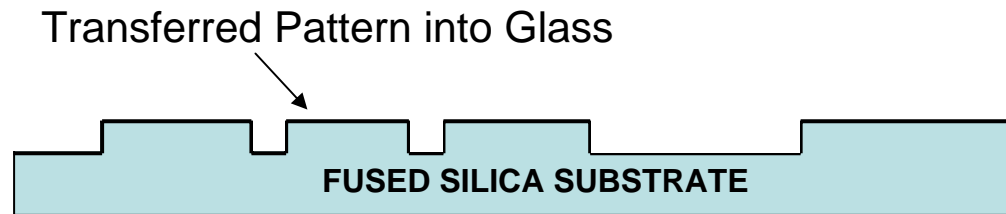
**Step 1:** Pattern Photoresist with MLT



**Step 2:** Ion Mill



**Result:** Pattern in Glass



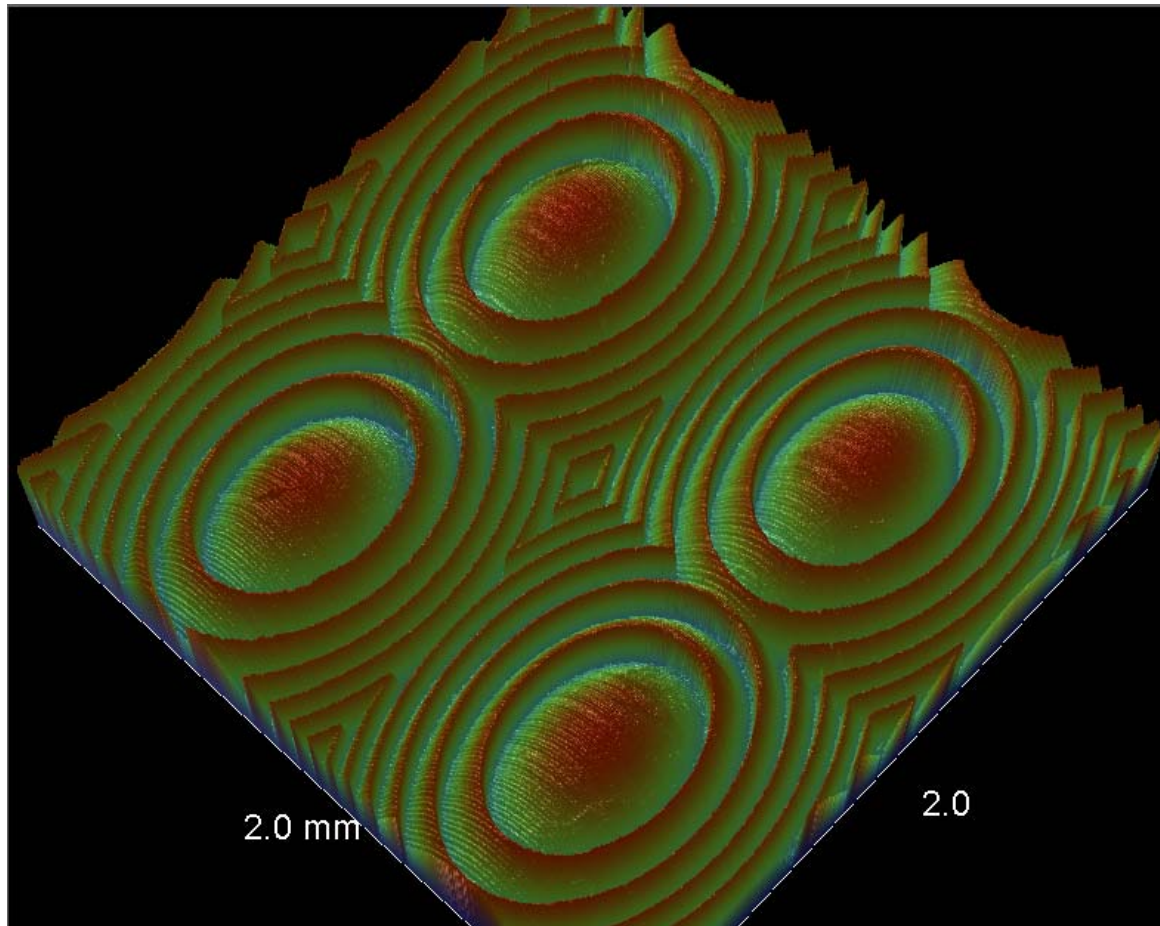


# Dry Pattern Transfer Using an Ion Mill

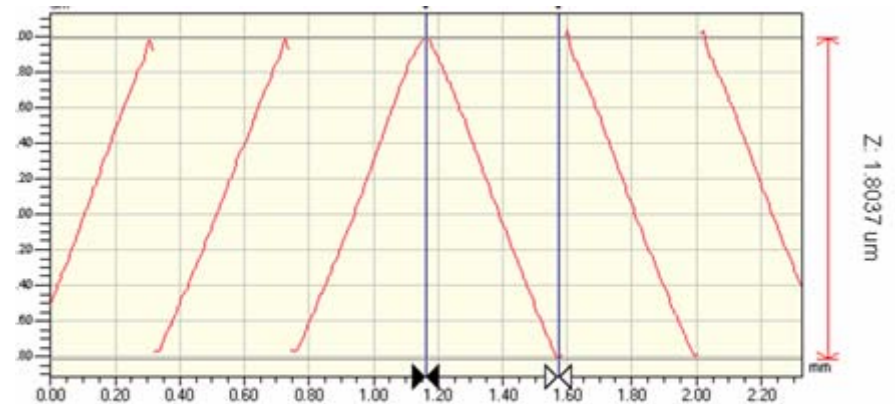
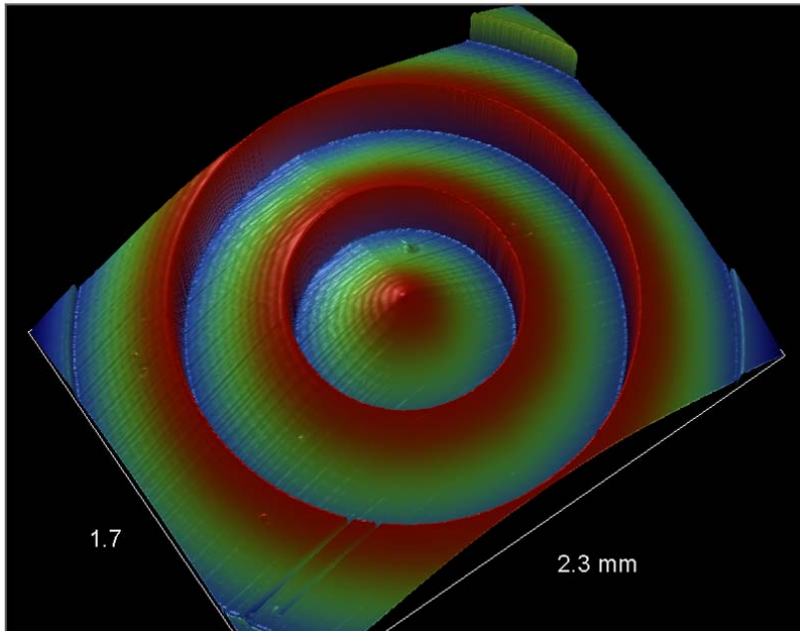
- Model:  
Commonwealth  
Scientific  
Corporation's  
Millatron VIII
- Uses a Kaufman  
(gridded) Design
- Electro-magnet  
type anode



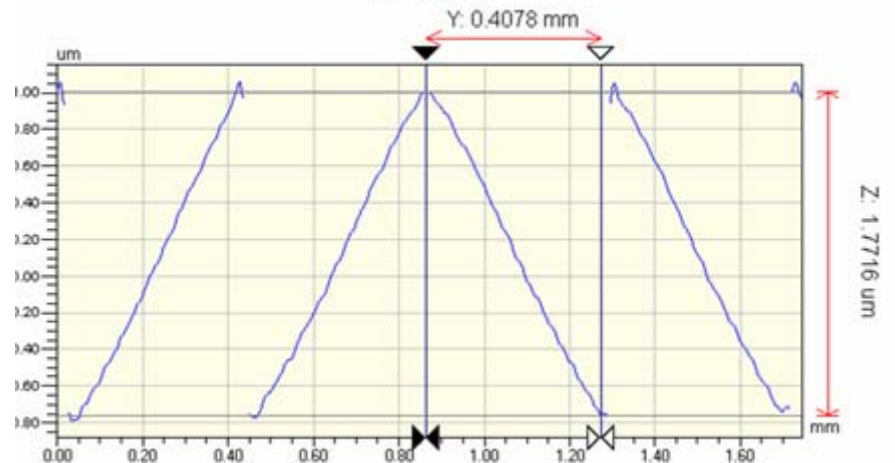
# Results – Astigmatic Fresnel Lens Array



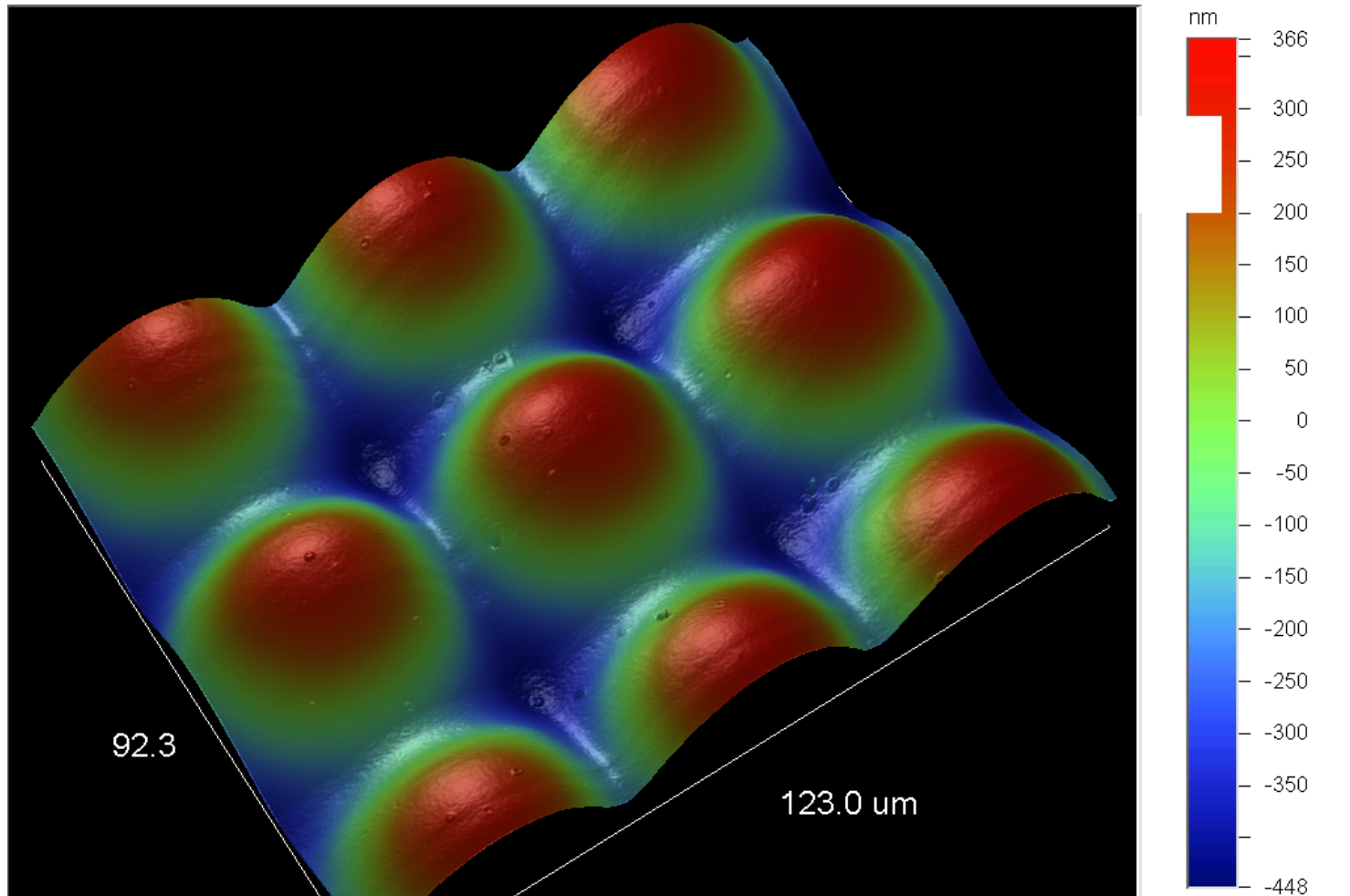
# Results – Diffractive Axicon



Y Profile



# Results – MicroLens Array (Direct Print)





# Lens Pattern in Photo-Resist (Crossed Lenses)



## 3-Dimensional Interactive Display

Date: 12/05/2007

Time: 13:50:16

### Surface Stats:

Ra: 911.16 nm

Rq: 978.85 nm

Rt: 3.16  $\mu\text{m}$

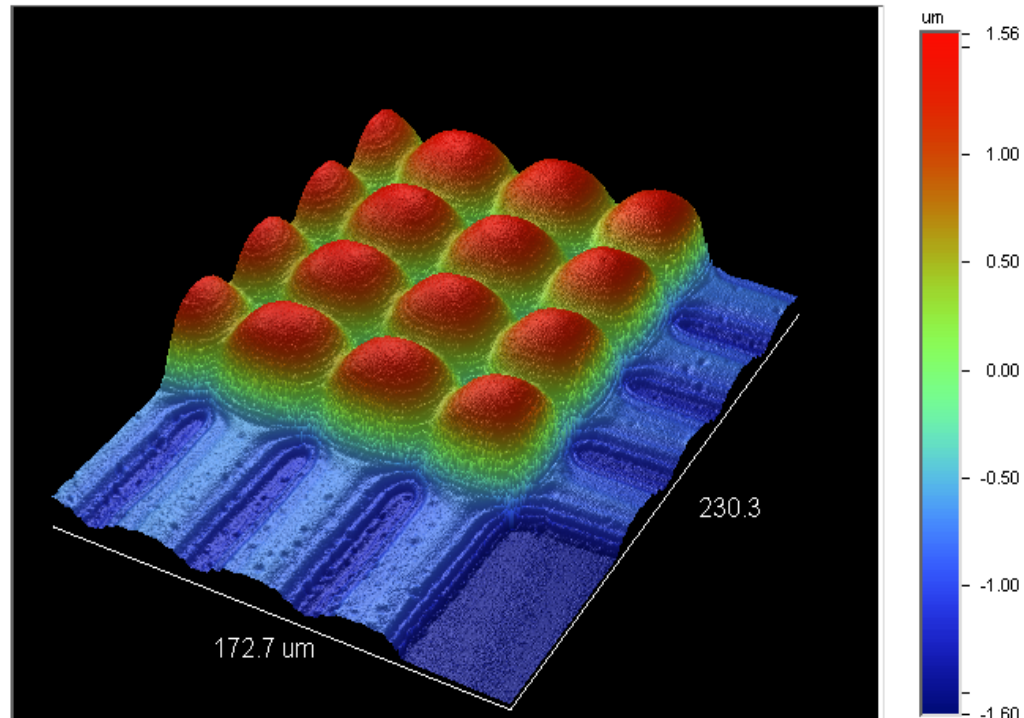
### Measurement Info:

Magnification: 27.52

Measurement Mode: VSI

Sampling: 359.78 nm

Array Size: 640 X 480

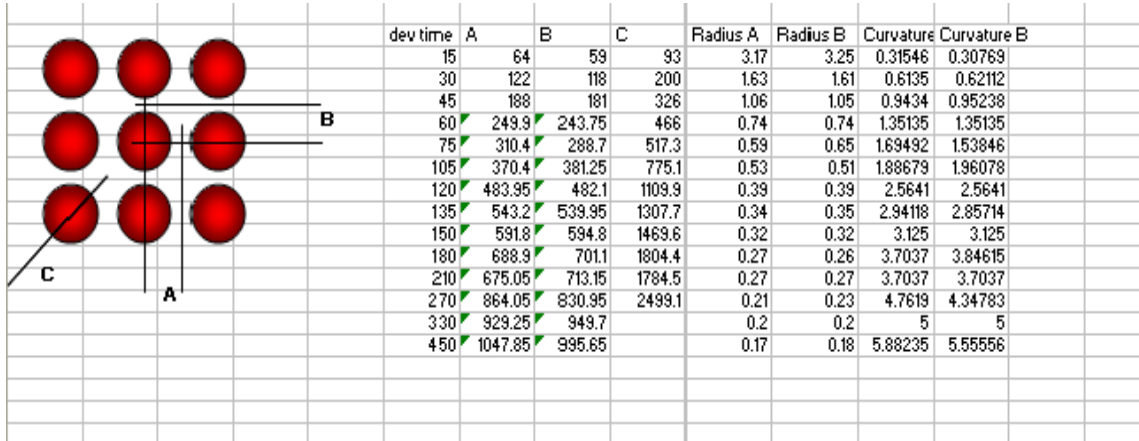


**Title:**

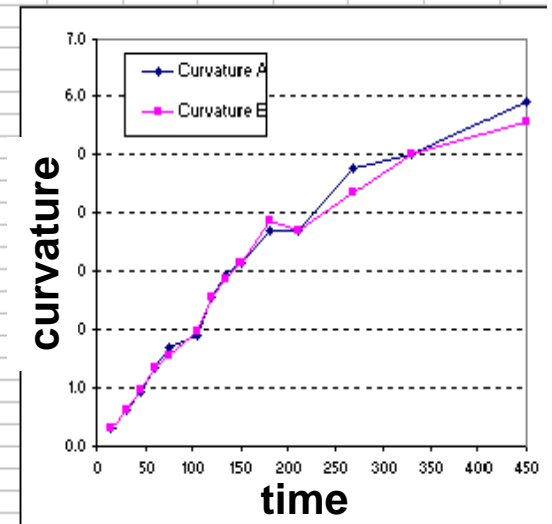
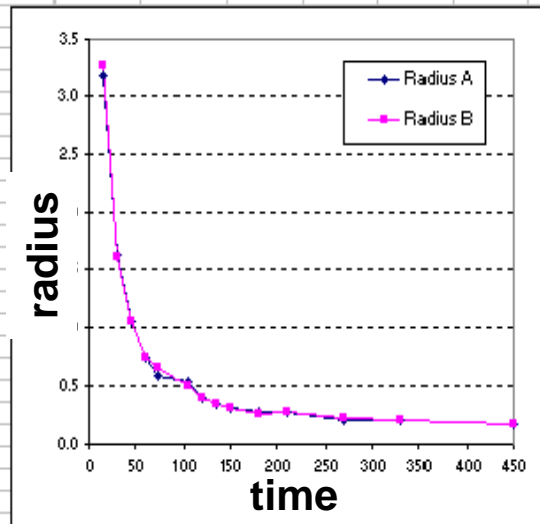
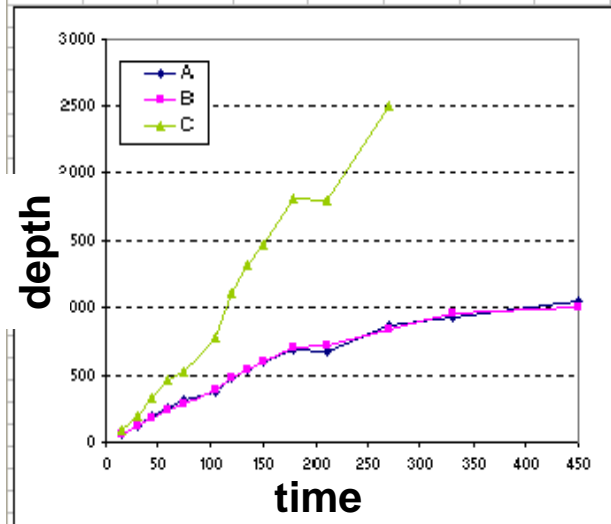
**Note:**



# Optimization of Lens Shape in Photo-Resist



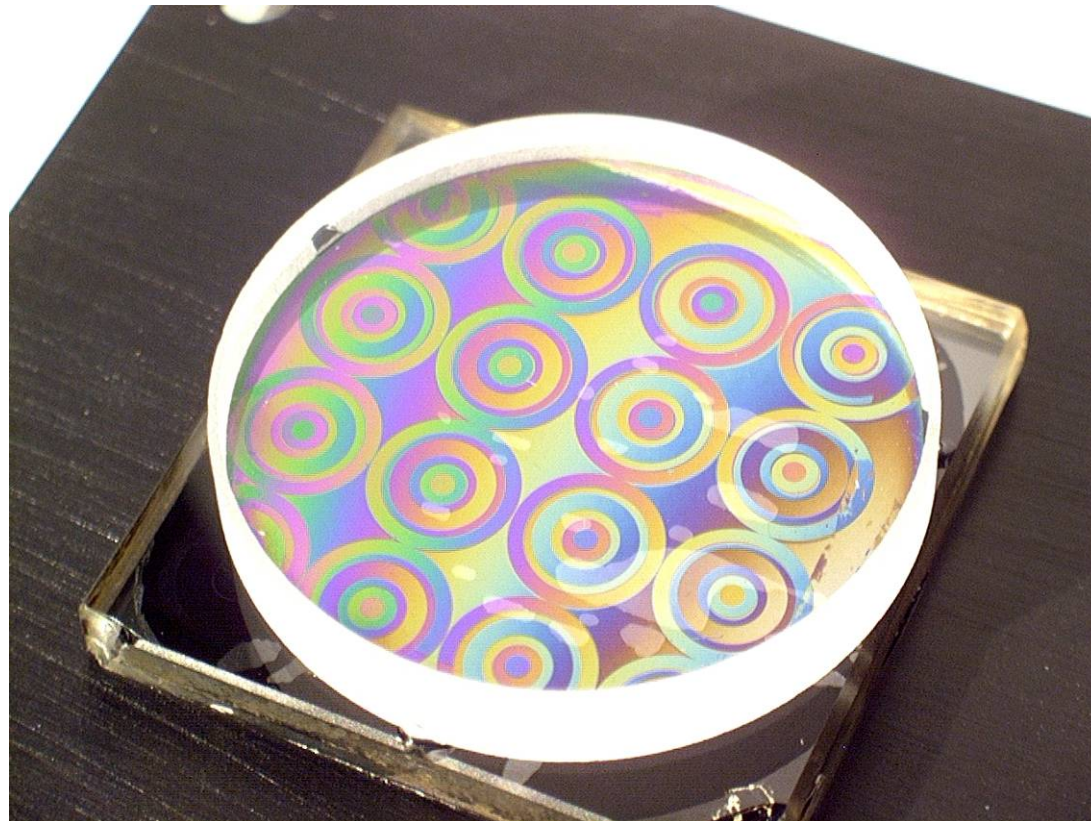
By modifying the development time, lens curvature can be adjusted.





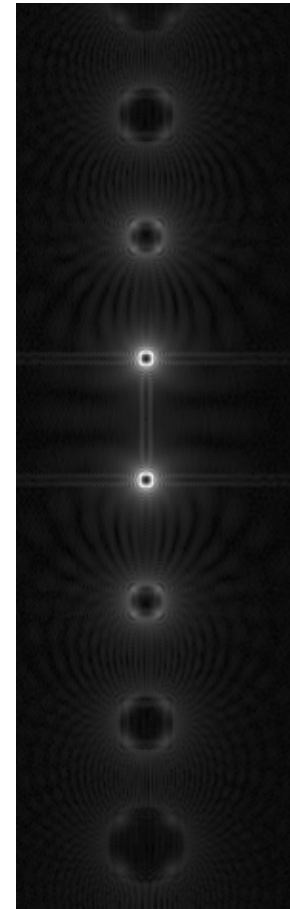
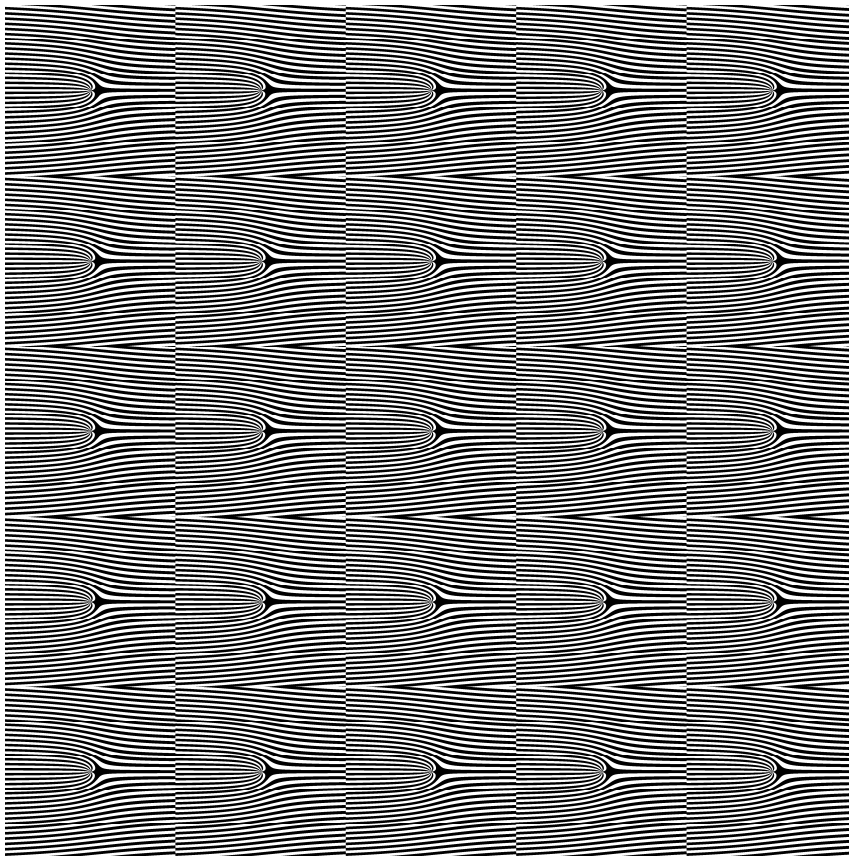
# Results – Spherical Aberration Compensator Array

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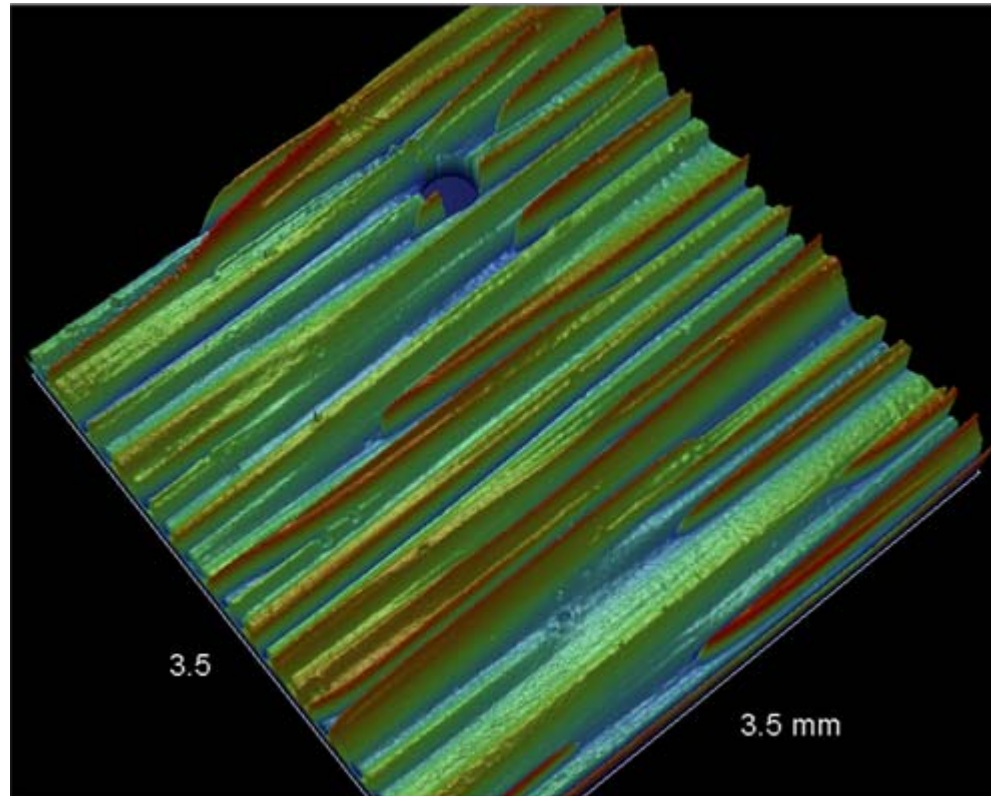




# Results – Diffractive Vortex Array



# Results – CGH Beam Diffuser



**Gray-Scale Diffuser for Peyghambarian Group  
Holographic Display Device. Large format (5" x 3")  
tiled array.**



# Future Work

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- We are looking forward to working with industry and academia on research and prototype projects.
- Desired Tool Improvements:
  - Optimization of beam stability servo
  - Focus calibration
  - Stage reconfiguration
  - Extended scan stages
  - Software improvements
  - Spot drift/quality control



# CGH/DOE Workshop



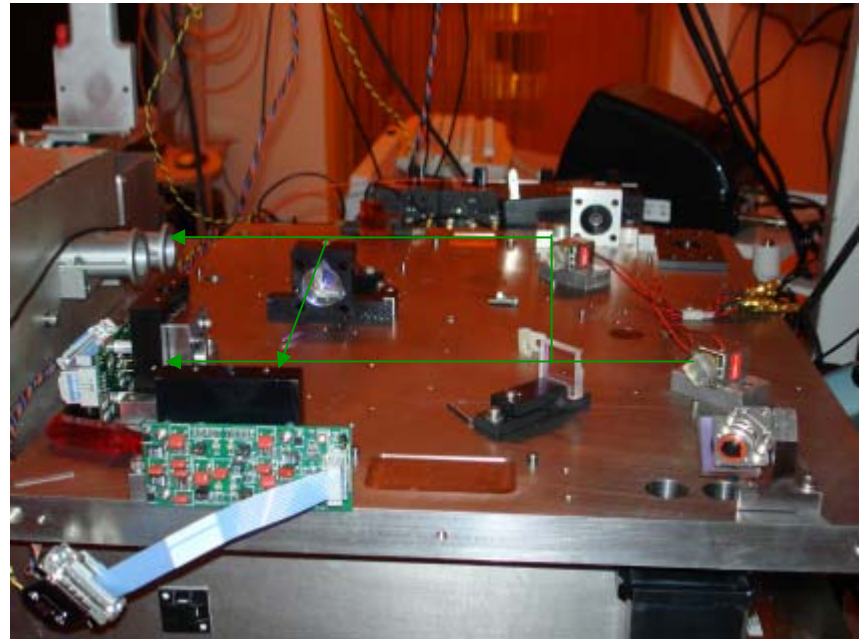
- 3-Day Workshop covers concepts and working knowledge of diffractive optical elements (DOEs) and computer generated holograms (CGHs).
- Extensive instruction on optical testing with CGHs.
- “Hands on” laboratories complement classroom instruction.
- Workshop Schedule:
  - March 17-21, 2008
  - March 16-20, 2009



# Thank You!

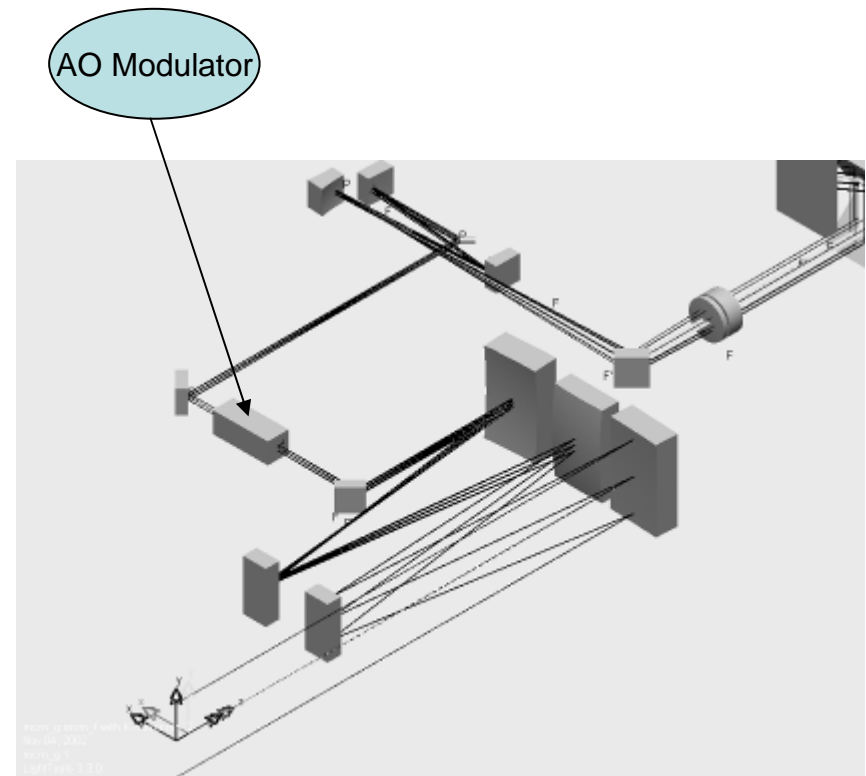
# Laser Beam Stabilization System

- **Pointing stability of laser systems is a question of major concern, since fluctuations of the lateral or angular beam position can cause pattern errors.**
- **A Servo Laser Beam Stabilization System was developed for beam drift compensation.**



# Modulation Subsystem

- The laser beam is compressed via a 3 mirror afocal telescope to get the right size before entering the acousto-optic modulator
- 8 channel acousto-optic modulator controls up to 8 beams of light (Only one is in use at this time)
- Each channel reaches 24 MHz of modulation frequency
- The beam is re-expanded via another 3 mirror afocal system to gain smaller focused spot size



# Working Stage

- Aerotech ALS 130 series
- Bi-directional repeatability to 0.1  $\mu\text{m}$
- Direct-drive linear motor for ultra-precise motion
- High-accuracy non-contact linear encoder
- Cross-roller bearings for smooth motion
- 90mm by 140mm stitch area

